

ABSTRACTTHIN LAYER OF HAFNIUM OXIDE AND DEPOSIT PROCESS

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A thin layer of hafnium oxide or stacking of thin layers comprising hafnium oxide layers for producing surface treatments of optical components, or optical components, characterised in that at least one layer of hafnium oxide is in amorphous form with a density less than  $8 \text{ gm/cm}^3$ .

The invention also relates to a process for producing a layer of amorphous hafnium oxide on a substrate, characterised in that the deposit is carried out without energy input to the substrate.

Figure 1